



Docket No.: M4065.0531/P531-A
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Werner Juengling, et al.

Examiner: Walter Lee Lindsay Jr.

Application No.: 10/673,362

Allowed: August 23, 2005

Filed: September 30, 2003

Group Art Unit: 2879

For: REVERSE METAL PROCESS FOR
CREATING A METAL SILICIDE
TRANSISTOR GATE STRUCTURE

APPLICANTS' COMMENTS ON EXAMINER'S STATEMENT OF REASONS FOR
ALLOWANCE

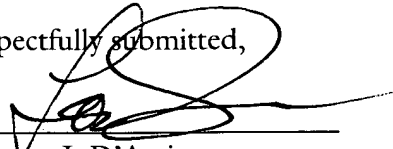
Commissioner for Patents
MS: Issue Fee
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Applicants agree only in part with the Examiner's reasons for allowance in that the prior art of record fails to disclose the limitations noted by the Examiner. However, the Examiner's statement does not reflect all of the language of each of the allowed claims. The totality of the language of each claim provides reasons for the allowance of each claim.

Dated: November 17, 2005

Respectfully submitted,

By 
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